

1509472

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**Application Information**

Title Line One:: PHOTOMASK BLANK, PHOTOMASK, METHODS OF  
Title Line Two:: MANUFACTURING THE SAME AND METHOD OF  
Title Line Three:: FORMING MICROPATTERN  
Title Line Four::

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Docket Number:: 105875

**Continuity Information**

>This application is a:: National Stage of  
Application One:: PCT/JP99/04124  
Filing Date:: July 30, 1999  
Patent Number::  
which is a::  
>>Application Two::  
Filing Date::  
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**Prior Foreign Applications**

Foreign Application One:: 10-217433  
Filing Date:: July 31, 1998  
Country:: JAPAN  
Priority Claimed:: YES  
Foreign Application Two::  
Filing Date::  
Country::  
Priority Claimed::  
Foreign Application Three::  
Filing Date::  
Country::  
Priority Claimed::